

Title (en)
Positive photoresist composition

Title (de)
Positiv arbeitende Fotoresistzusammensetzung

Title (fr)
Composition pour photoréserve de type positif

Publication
EP 0740213 A3 19980701 (EN)

Application
EP 96106692 A 19960426

Priority
• JP 10430795 A 19950427
• JP 669496 A 19960118

Abstract (en)
[origin: EP0740213A2] There are provided a positive photoresist composition comprising an alkali-soluble resin and a 1,2-naphthoquinonediazide-5-(and/or -4-)sulfonic ester of a tetrahydroxy compound having a specific structure, said ester component having a pattern area in the high-performance liquid chromatography determined using ultraviolet rays of 254 nm accounting for 50% or more of the entire pattern area and a positive photoresist composition comprising an alkali-soluble resin and 1,2-naphthoquinonediazide-5-(and/or -4-)sulfonic esters of two kinds of specific polyhydroxy compounds. The positive photoresist is suitable for ultrafine working and ensures high sensitivity and high resolution and is improved with respect to film thickness dependency and standing wave.

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G03F 7/022

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CPC (source: EP KR US)
G03F 7/016 (2013.01 - KR); **G03F 7/022** (2013.01 - EP US)

Citation (search report)
• [AD] JP H02296248 A 19901206 - NIPPON ZEON CO
• [AD] EP 0573056 A2 19931208 - SUMITOMO CHEMICAL CO [JP]
• [AD] EP 0440238 A2 19910807 - FUJI PHOTO FILM CO LTD [JP]

Designated contracting state (EPC)
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